ARTICLE

SIMULATION STUDY OF THE SCALING EXPONENTS FOR COMPETITIVE GROWTH BETWEEN BALLISTIC DEPOSITION AND RANDOM DEPOSITION WITH SURFACE RELAXATION IN 2+1 DIMENSIONS

SUDEEP KUMAR DAS*

For distinct sets of values of the competitive growth parameter and the system size, rough surfaces were created by computer simulation for competitive growth between Random Deposition with Surface Relaxation and Ballistic Deposition. The evolution appeared with two regimes of time growth with two acutely different slopes and a saturation regime with zero slopes. The reliance of the scaling exponents and the fractional porosity on the competitive growth parameter and system size is reported. The scaling exponents are found to have some deviation from the relevant universality classes.